Korean International Semiconductor Conference & Exhibition
on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[WeB2] Advanced Etch II	
Session Date	November 12 (Wed.), 2025
Session Time	14:10-15:35
Session Room	Room B (Grand Ballroom 1, 2F)
Session Chair	Dr. Dongsoo Lee (Lam Research Korea, Korea)

[WeB2-1] [Invited] **14:10-14:40**

Advanced Patterning of Metal Oxide Semiconductors for Memory Applications: IBE, RIE, and ALE Approaches

Jie Li, Shreya Kundu, Laurent Souriau, Yiqun Wan, Attilio Belmonte, and Katia Devriendt (imec, Belgium)

[WeB2-2] [Invited] **14:40-15:05**

r-Wave Resonance-Enhanced ICP Etcher for High-Precision Dry Etching

Taeho Shin (ICD Ltd., Korea)

[WeB2-3] **15:05-15:20**

Crystalline Ultra-Thin High-K Films Enabled by Fluorine-Radical-Based Atomic Layer Etching

Somyeong Shin, Chang Kyu Lee, Chan Lee, Hyeonjin Cha, Byung Chul Cho, Ju Hwan Park (WONIK IPS, Korea), Misoo Kim, Khabib Khumaini, Hye-Lee Kim, Gyejun Cho, Yewon Kim, Won-Jun Lee (Sejong Univ., Korea), and Min Kim (WONIK IPS, Korea)

[WeB2-4] **15:20-15:35**

Study on SiO_2 Atomic Scale Etching Using Selective Control of Ar Metastable Atom Generation

Chang-Min Lim, Jae-Hwi Kim, Hyeon-Jun Cho, Young Don Kim, and Chin-Wook Chung (Hanyang Univ., Korea)